

PATENT APPLICATION**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of

Akira SAKAI et al.

Group Art Unit: 2829

Application No.: 10/807,235

Examiner: E. Pert

Filed: March 24, 2004

Docket No.: 119232

For: METHOD FOR FABRICATING A METALLIC OXIDE OF HIGH DIELECTRIC
CONSTANT, METALLIC OXIDE OF HIGH DIELECTRIC CONSTANT, GATE
INSULATING FILM AND SEMICONDUCTOR ELEMENT

SUPPLEMENTAL AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

As a supplement to the Amendment filed on December 22, 2004, please further
consider the following:

Amendments to the Claims as reflected in the listing of claims; and

Remarks.

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February 17, 2005

FACSIMILE TRANSMISSION COVER SHEETTo: Examiner Evan Pert
(571) 273-1969

From: Leana Levin

Your Ref.: 10/807,235

Our Ref.: 119232

Number of Pages Sent (Including cover sheet): 8

Prepared By: ll

Comments:

Dear Examiner Pert:

As requested, attached is a courtesy copy of the Supplemental Amendment filed in the U.S. Patent and Trademark Office on February 16, 2005. Please feel free to contact me if you have any questions at (314) 621-8383.

Best regards,

Leana Levin

Leana Levin, Reg. No. 51,939

Sent by: ll

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